

AMENDMENTS TO THE CLAIMS

Claim 1 (Original) A substrate processing system comprising:

- a gas supply source for supplying a process gas containing a reactive substance;
- a reservoir tank connected to said gas supply source for reserving said process gas;
- a reactor for exposing a substrate placed therein to said process gas;
- a first circulation pipe for introducing the process gas inside said reactor into said reservoir tank;
- a second circulation pipe for introducing at least part of the process gas in said reservoir tank into said reactor; and
- a flow regulating valve disposed in said second circulation pipe for regulating the amount of process gas to be introduced into said reactor.

Claim 2 (Original) The substrate processing system of Claim 1, further comprising a pump for drawing said process gas from said reactor and introducing it into said reservoir tank through said first circulation pipe.

Claim 3 (Currently Amended) The substrate processing system of Claim 1 ~~or 2~~, further comprising a second gas supply source for supplying a second process gas to said reactor such that the second process gas bypasses said reservoir tank, said second process gas containing a reactive substance different from that contained in said first process gas.

Claim 4 (New) The substrate processing system of Claim 2, further comprising a second gas supply source for supplying a second process gas to said reactor such that the second process gas bypasses said reservoir tank, said second process gas containing a reactive substance different from that contained in said first process gas.